

# Research towards a possible upgrade of the LHCb VErtext LOcator

## Overview

- The LHCb detector and the VELO
- VELO sensor performance
- Possible upgrade solution
  - Czochralski Silicon
- Current status



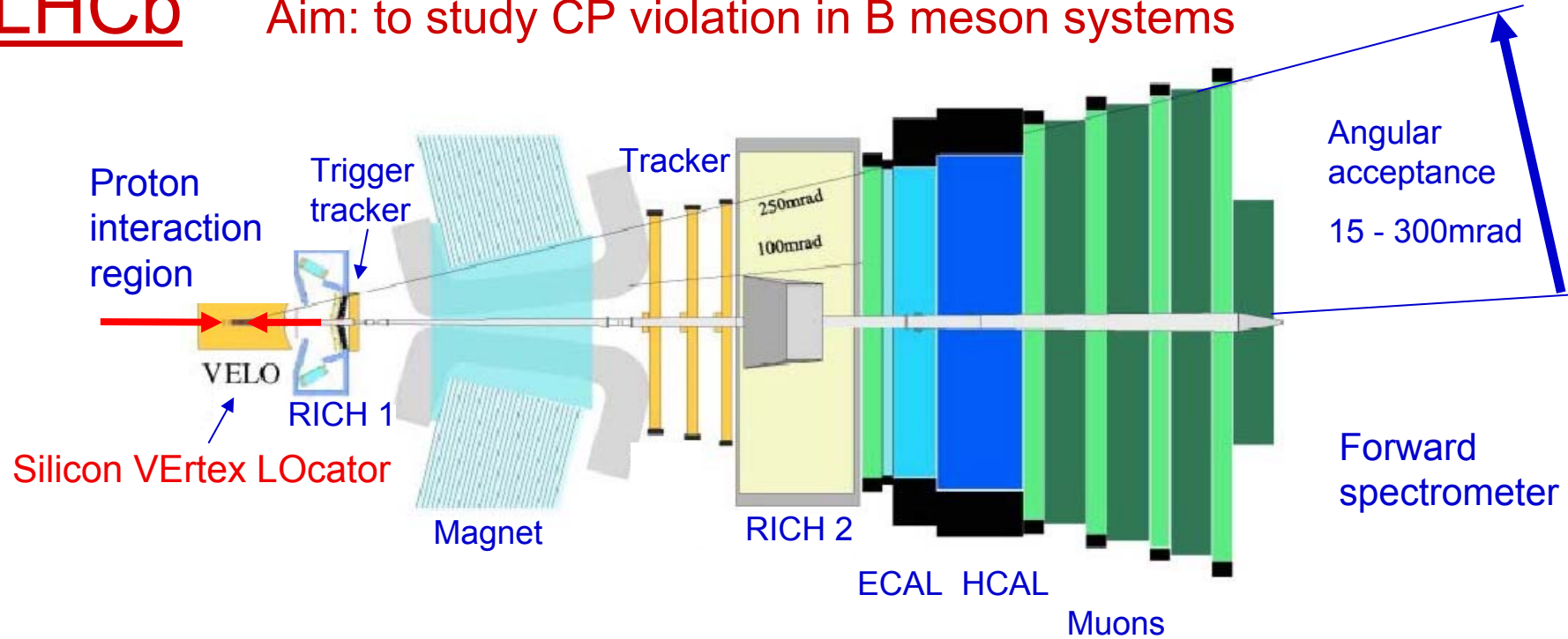
Alison G Bates  
The University of Glasgow / CERN



IoP HEPP Conference, University College Dublin  
21<sup>st</sup>-23<sup>rd</sup> March 2005

# LHCb

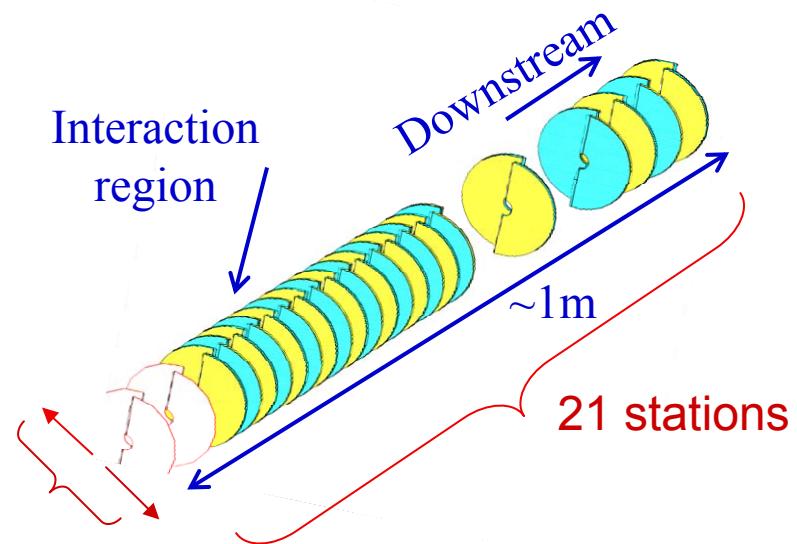
Aim: to study CP violation in B meson systems



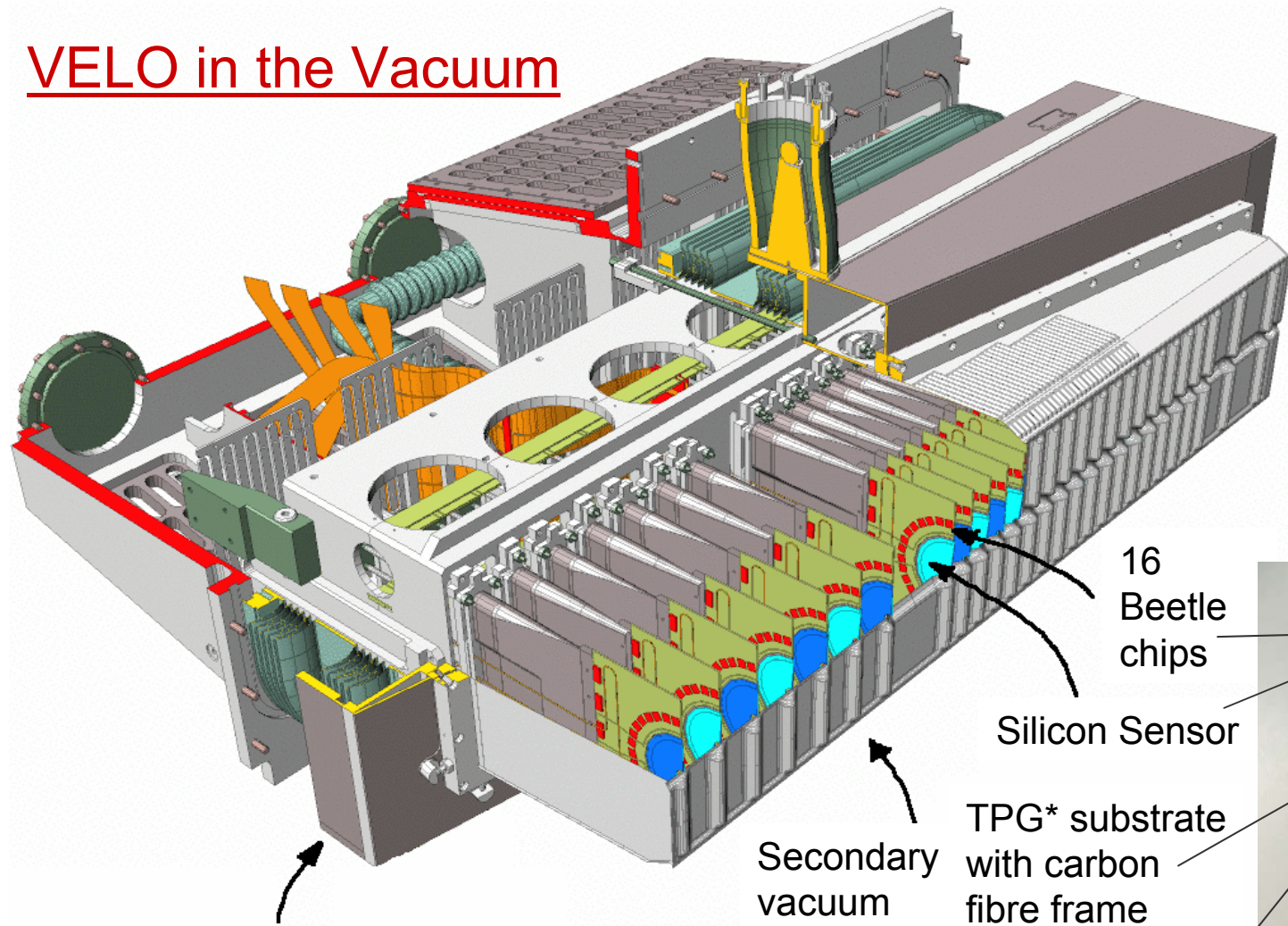
## LHCb VERtEx Locator

- 21 silicon tracking stations placed along the beam direction
- 2 retractable detector halves for beam injection periods (up to 30 mm)

Retractable detector halves



# VELO in the Vacuum



Double sided modules

(1 x R and 1 x  $\Phi$  sensor)

Retracting Detector Half

Silicon operating temperature  $-7^{\circ}\text{C}$

Secondary vacuum Chamber

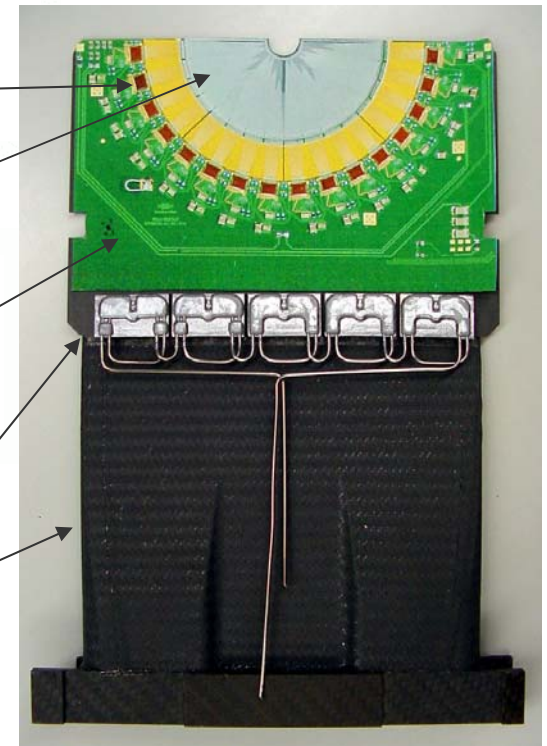
TPG\* substrate with carbon fibre frame

Cooling contacts

Carbon fibre paddle

16 Beetle chips

Silicon Sensor



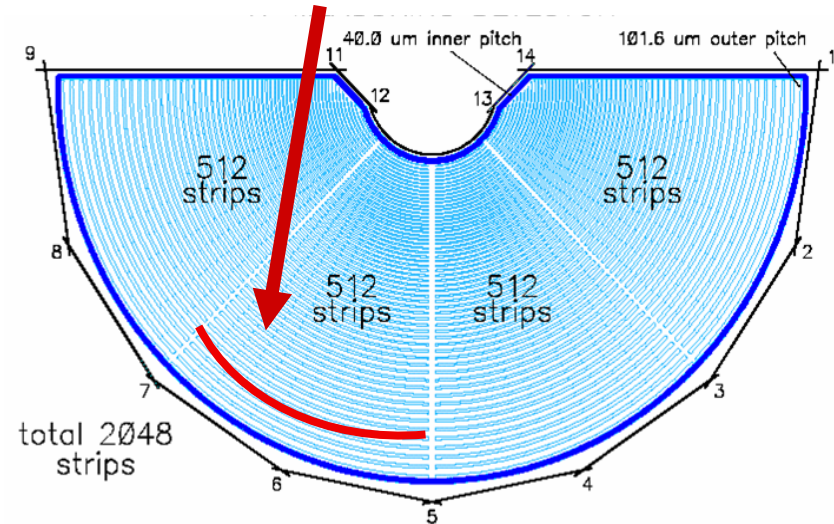
\*Thermalised Pyrolytic Graphite

# VELO Sensor design

- 2 sensor types: R and  $\Phi$ 
  - R measuring gives radial position
  - $\Phi$  measuring gives an approximate azimuthal angle
- Varying strip pitch
  - 40 to 102  $\mu\text{m}$  (R – sensor)
  - 36 to 97  $\mu\text{m}$  ( $\Phi$  – sensor)
- First active silicon strip is 8.2 mm from the beam line
- n<sup>+</sup>-on-n DOFZ silicon
  - minimises resolution and signal loss after type inversion
- Double metal layer for detector readout

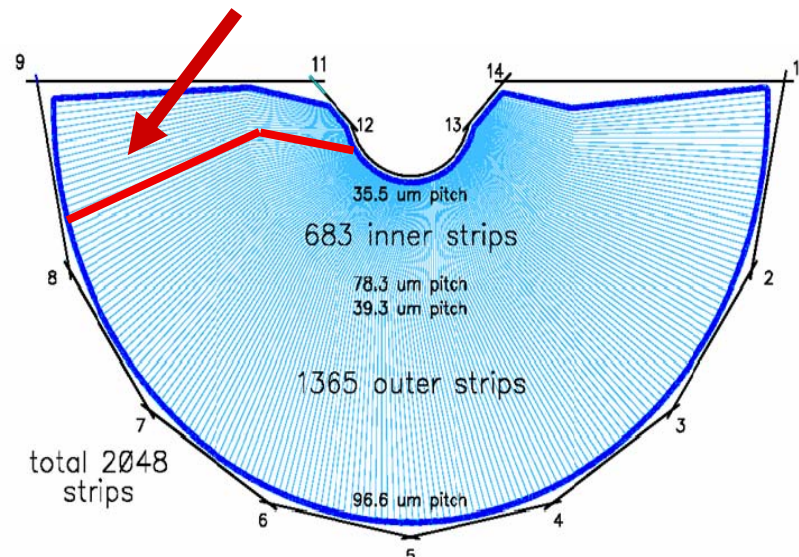
R-measuring sensor:

(concentric strips)

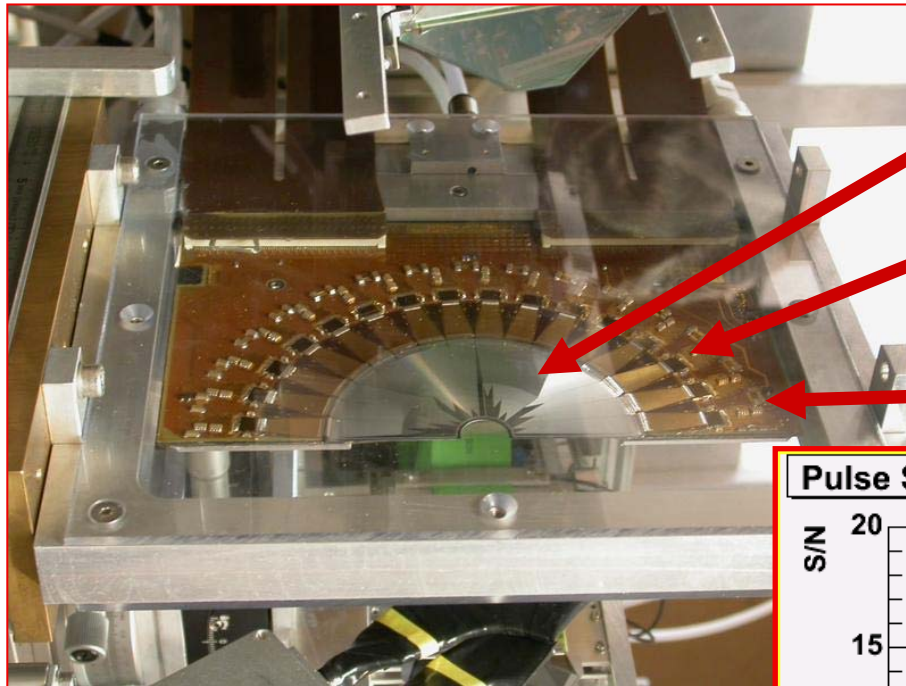


$\Phi$ -measuring sensor:

(Radial strips with a stereo angle)



# 2004 test beam results



300 $\mu$ m n<sup>+</sup>-on-n R sensor

16 readout chips  
(Beetle 1.3)

Prototype hybrid (K03)

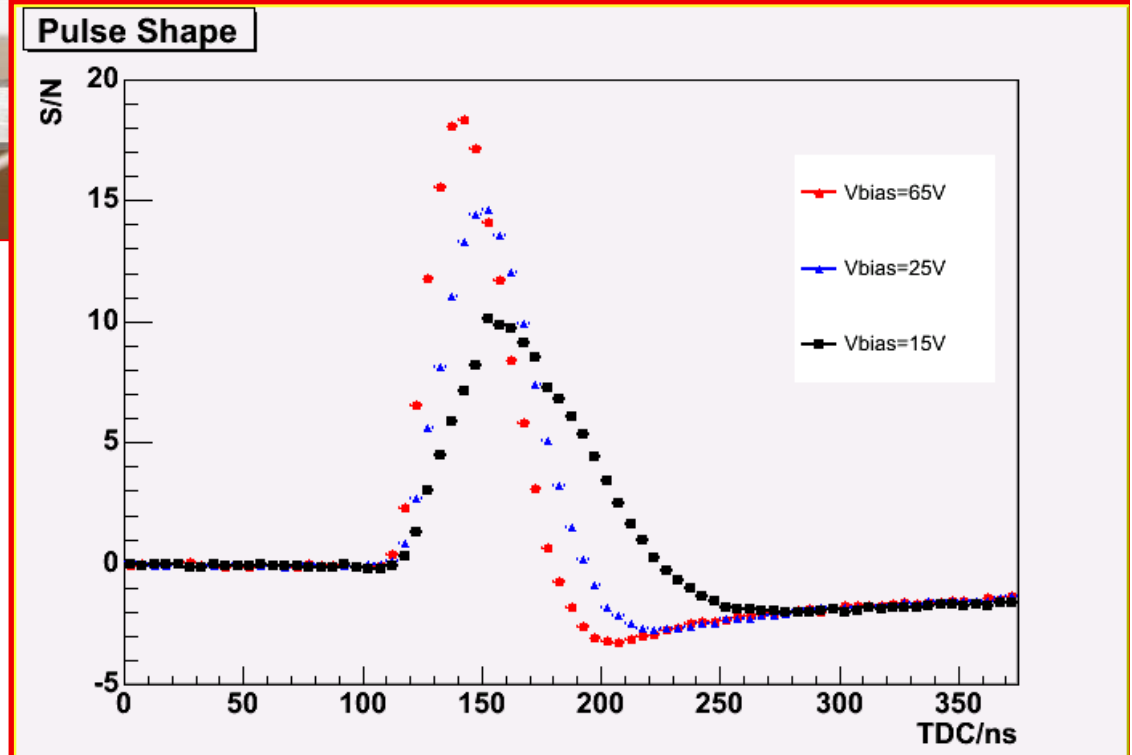
300 $\mu$ m S:N = 19:1

200 $\mu$ m S:N = 13.5:1

**spillover:** signal at 25ns after peak in % of the peak signal

< 30% (100V bias)

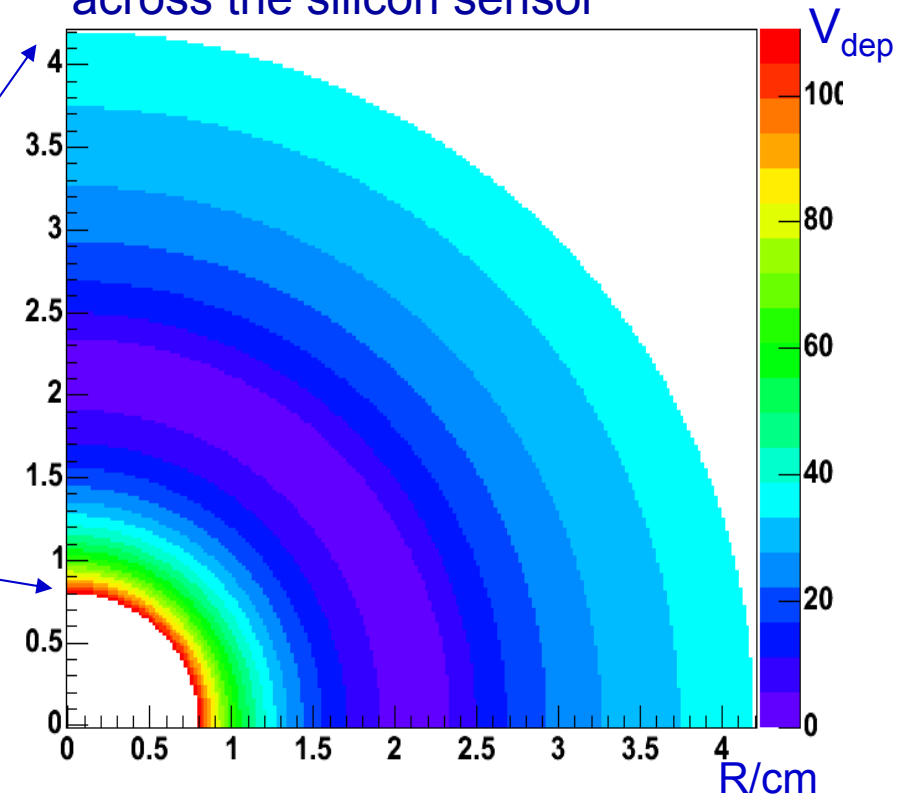
(30% is the maximum before displaced vertex trigger performance degraded.)



# VELO environment

- VELO sensors operate in a harsh non-uniform radiation environment
  - fluence to outer regions  $5 \times 10^{12} n_{eq./cm^2}$
  - fluence to inner regions  $1.3 \times 10^{14} n_{eq./cm^2}$
- Estimated to survive 3 years (~2010)
  - A replacement/upgrade is foreseen

Illustration of the depletion voltage across the silicon sensor

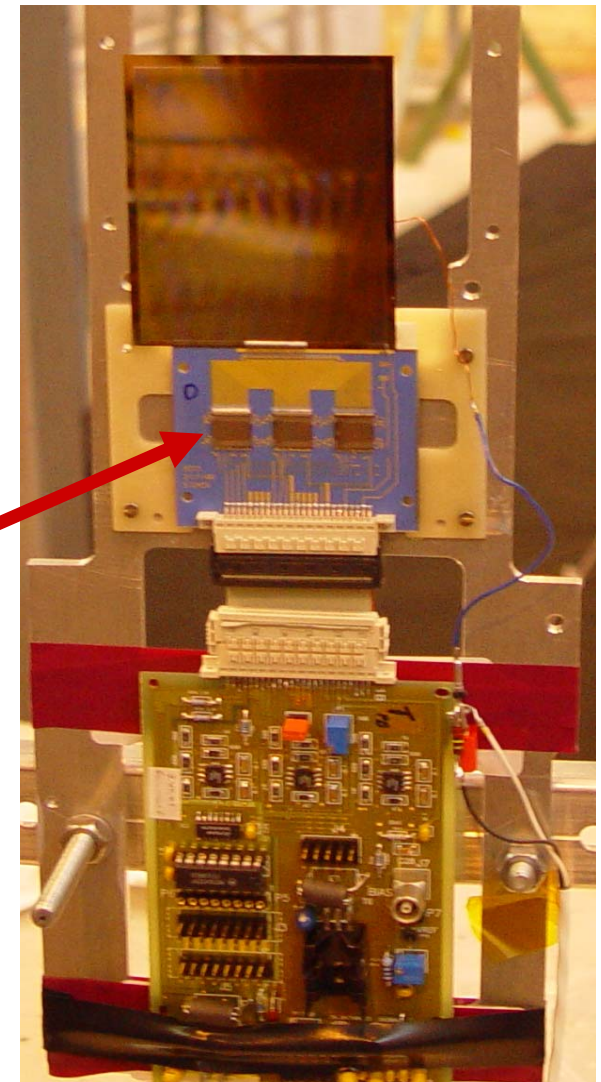


If the sensors move closer to the beam OR we increase the luminosity then a more radiation hard silicon solution is required.

# Possible upgrade choices for the silicon

n<sup>+</sup>-on-p, pixels, 3D, ...many possibilities

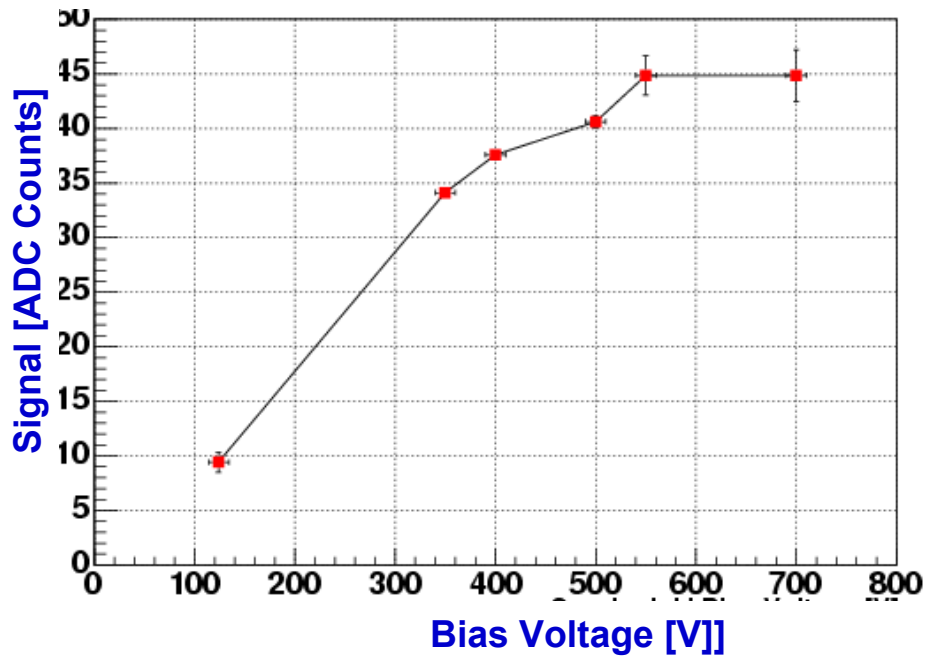
- Magnetic Czochralski silicon
  - Standard industrial method of producing silicon
    - Cheap
    - Naturally high Oxygen content
      - more radiation hard?
- Test beam at the CERN SPS of a MCz detector\* before and after irradiation
  - LHC speed electronics (40 MHz)  
(3 SCTA (analogue) chips)
  - p<sup>+</sup>-on-n MCz material
  - Area<sub>read out</sub> = 6.1 x 1.92 cm
  - 380 μm thick, 50 μm pitch



\* Many thanks to the Helsinki Institute of Physics for the MCz detector

# MCz test beam results

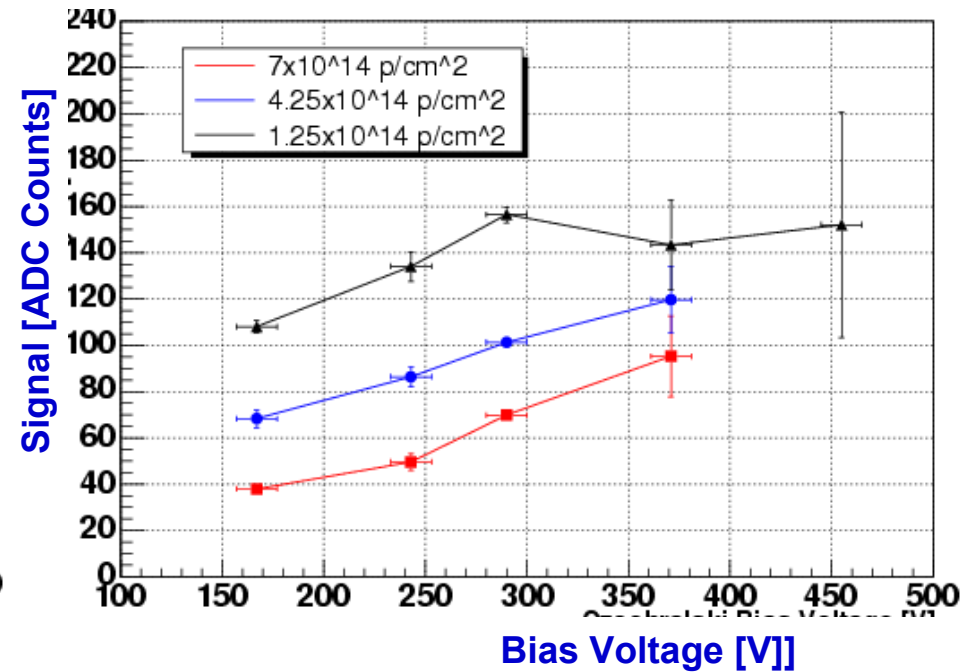
## Unirradiated Detector



✓ Depleted the detector (~550 V)  
(CV measured  $V_{dep} \sim 420$  V)

$S / N > 23.5 + 2.5$   
(380  $\mu\text{m}$  thick)

## Irradiated Detector

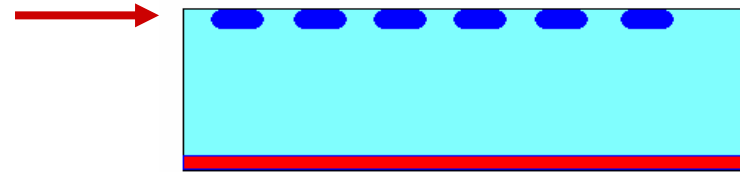


- $1.3 \times 10^{14}$  24 GeV p/cm<sup>2</sup> S/N = 15
- $4.3 \times 10^{14}$  24 GeV p/cm<sup>2</sup> S/N = 11  
(under depleted)
- $7.0 \times 10^{14}$  24 GeV p/cm<sup>2</sup> S/N = 7  
(under depleted)



## Further MCz benefits

- The VELO currently uses  $n^+$ -on-n DOFZ silicon detectors



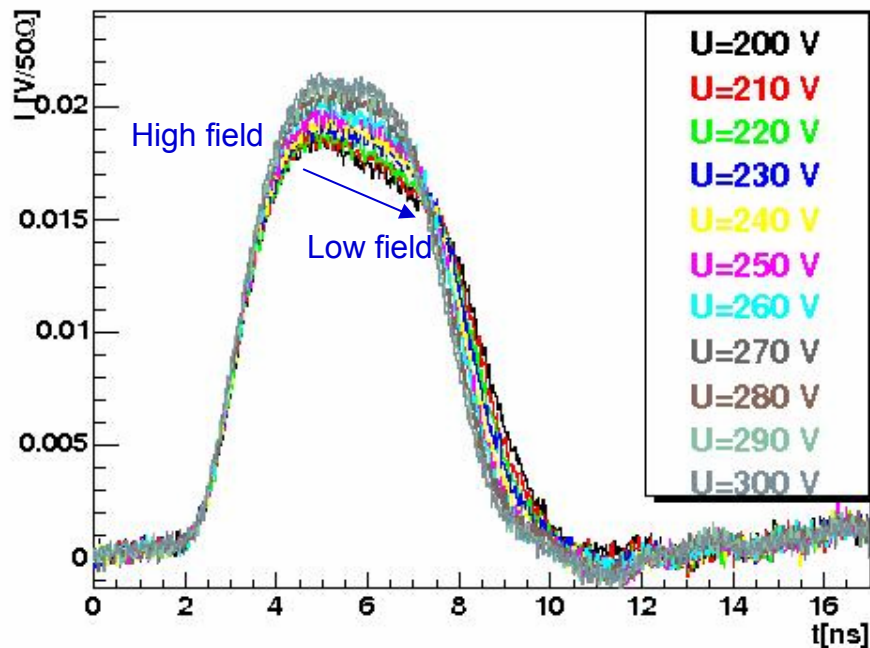
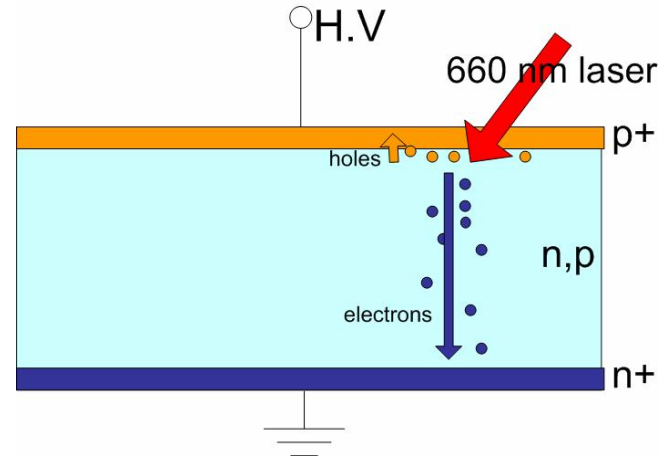
- This is necessary because we want the silicon to have the high electric field always on the strip side in order to prevent loss of resolution and signal after *type inversion* and when operated *under-depleted*
- However,  $n^+$ -on-n is expensive and restricts the choice of processing company (requires double-sided processing)

We have found that MCz **does not type invert** using the **Transient Current Technique** (measured to  $5 \times 10^{14}$  p/cm<sup>2</sup>)

# Transient Current Technique

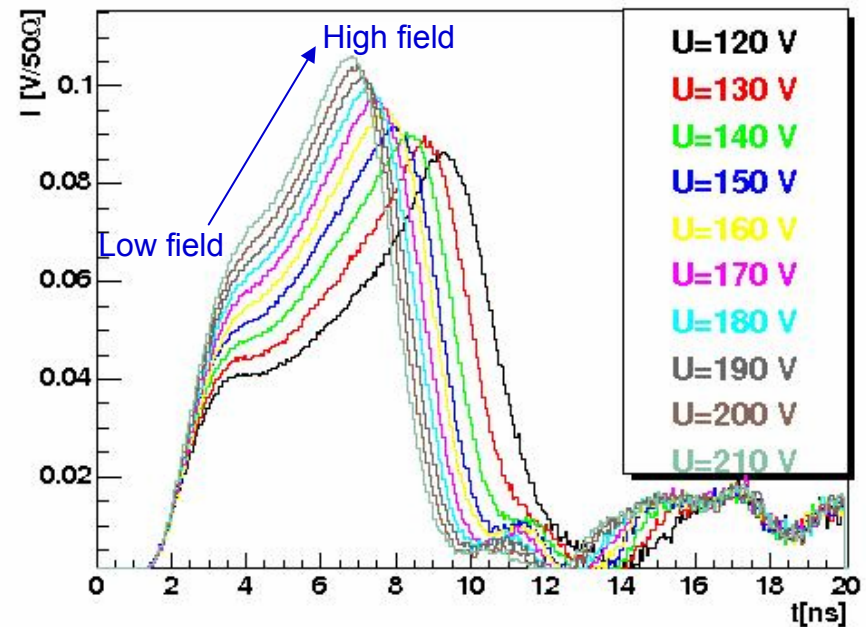
- experiment which probes the electric field inside the detectors

type inversion in FZ silicon



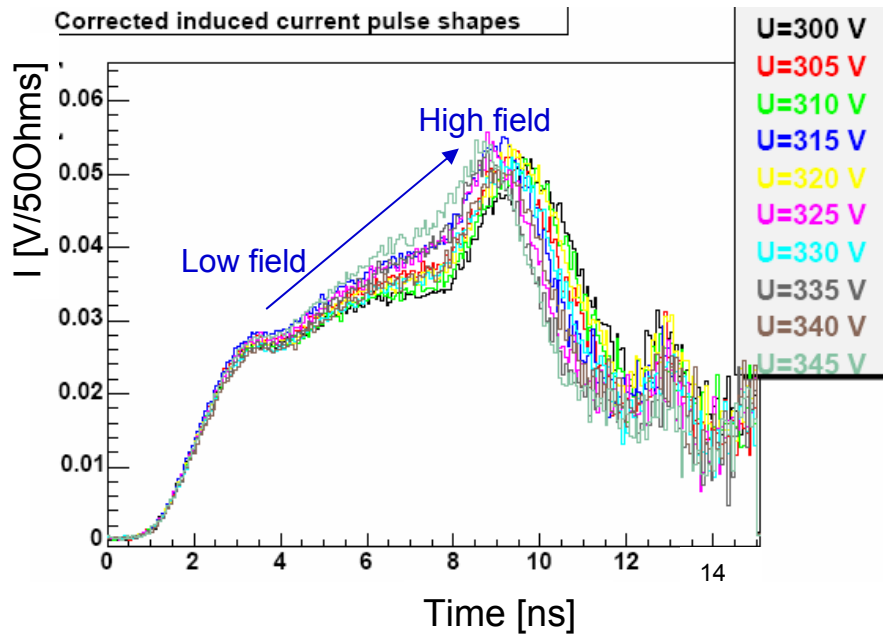
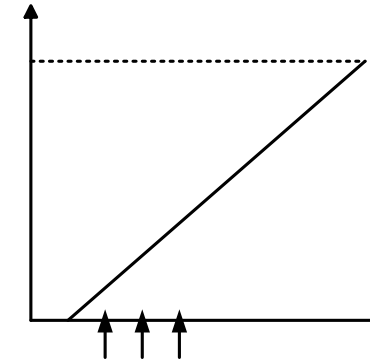
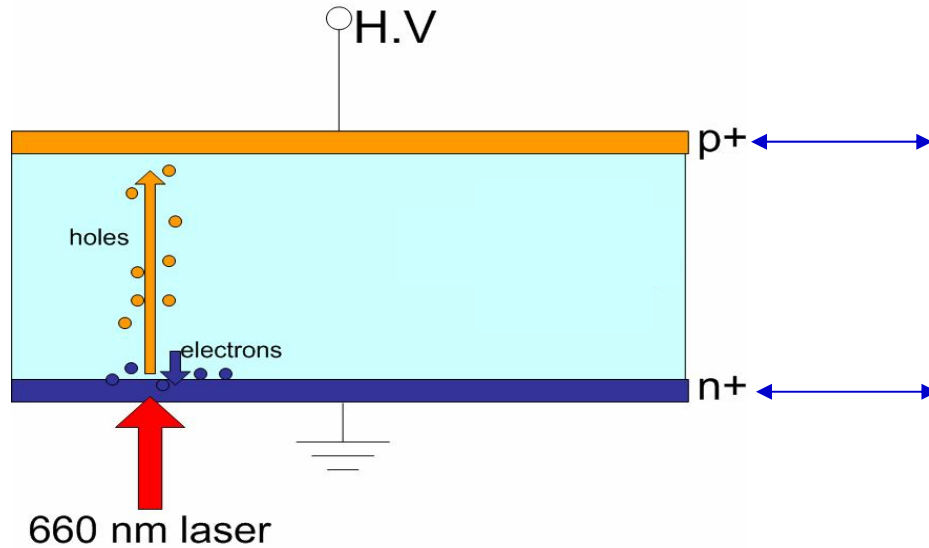
$\Phi = 1.74 \times 10^{13}$  24 GeV/c p

Corrected induced current pulse shapes



$\Phi = 3.61 \times 10^{14}$  24 GeV/c p

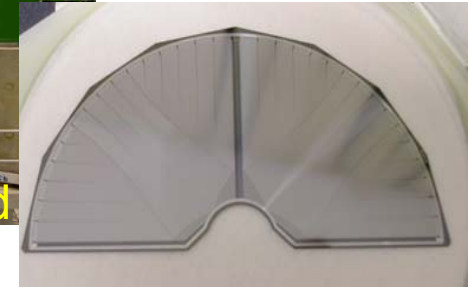
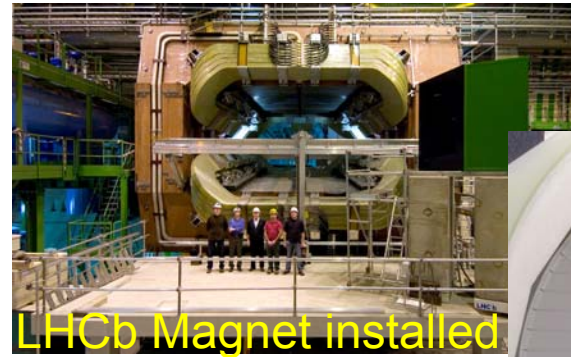
# TCT in MCz



MCz silicon always has the high field on the strip side of the detector

=> standard p<sup>+</sup>-on-n MCz detectors could replace the VELO n<sup>+</sup>-on-n DOFZ silicon, however, further investigation of the radiation tolerance of MCz is required

# Status & Conclusions



- The VELO is moving from the last prototype testing to sensor production
- Looking forward to physics in 2007
- Research started on upgrade possibilities for the LHCb detector
- There are many possibilities for the VELO silicon upgrade in 2010
  - n<sup>+</sup>in-p FZ silicon
  - 3D detectors
  - Czochralski Silicon

first operation of full size MCz sensor with LHC speed electronics in test beam

- further test beam studies planned

non-inversion of MCz material under radiation demonstrated

- additional microscopic studies underway

# Back Up Slides

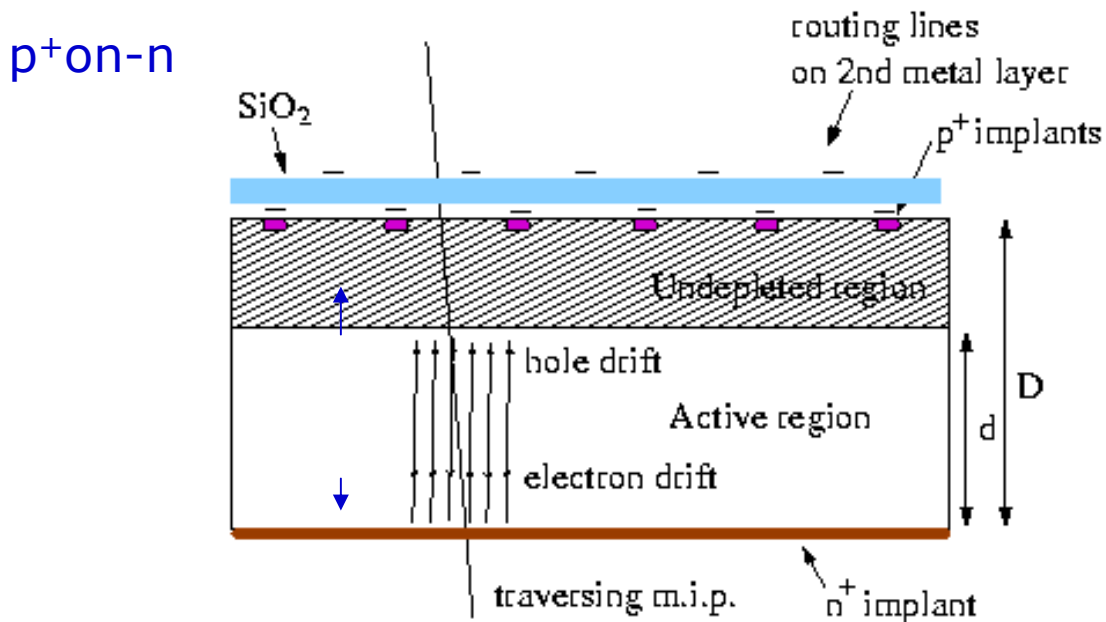


# A VELO story

The standard silicon detectors are p<sup>+</sup>on-n silicon detectors.

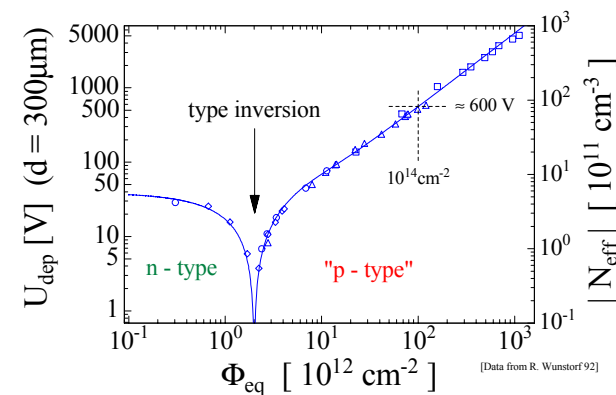
Now consider what happens as the expt. proceeds and the radiation damage increases....

- Within the first few months the bulk material will still be n-type. The electric field grows from the front p<sup>+</sup> implant. The V<sub>fd</sub> will be decreasing, hence no problems to deplete the sensor.
- Depending on the particle flux the bulk will eventually become p-type and the electric field will 'grow' from the back n<sup>+</sup> implant now. The V<sub>fd</sub> is increasing every day hence at some point the detector will be operated under-depletion... in which case:



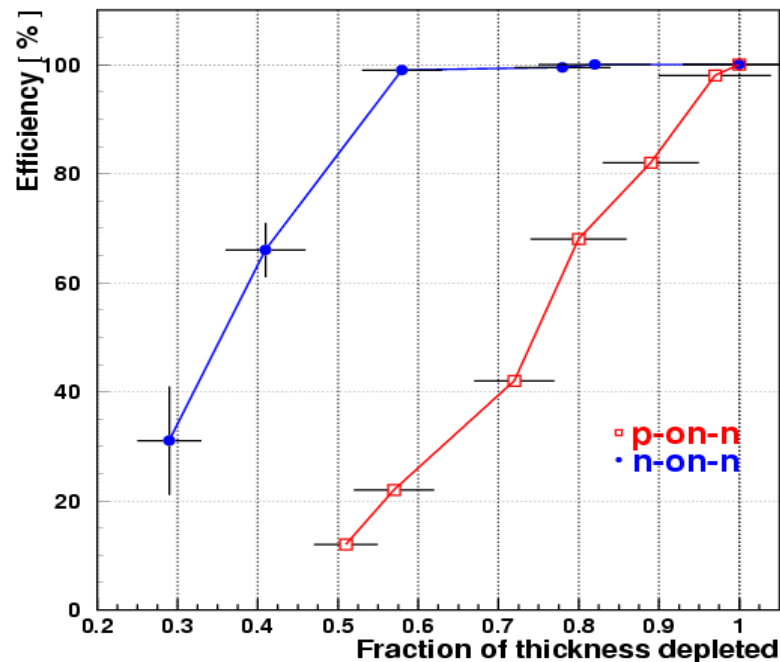
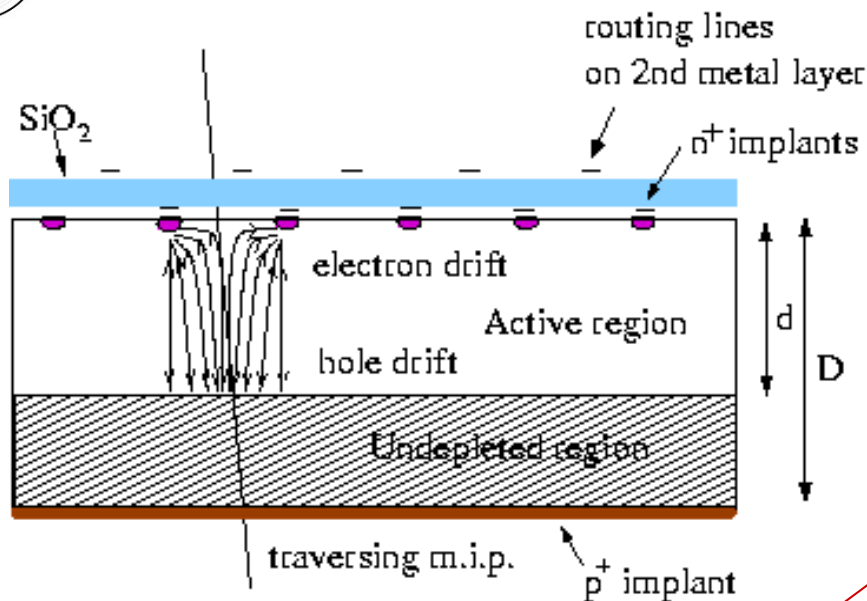
p-on-n silicon, under-depleted:

- Charge spread – degraded resolution
- Charge loss – reduced CCE





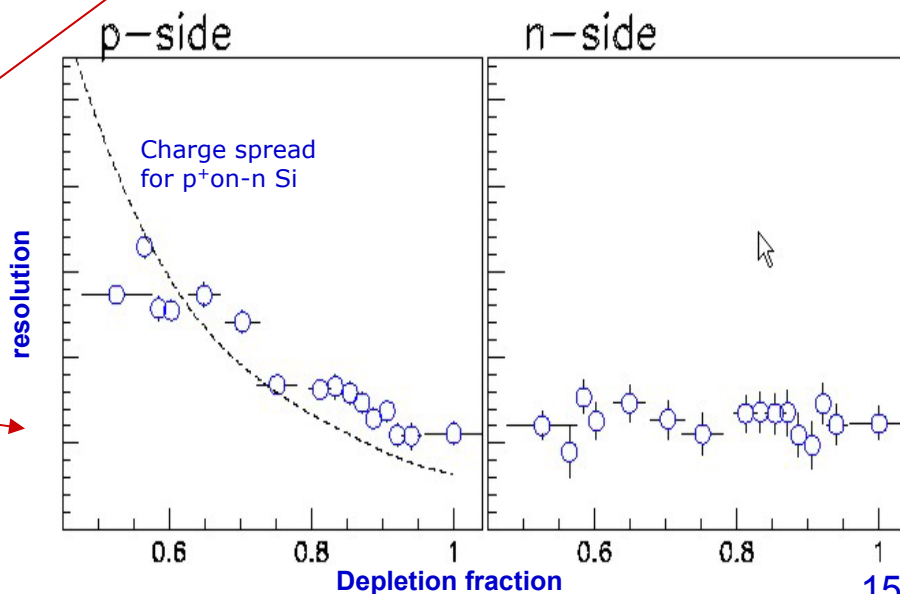
# n<sup>+</sup>on-n



n-on-n silicon, under-depleted:

- Limited loss in CCE
- Less degradation with under-depletion

For LHCb n<sup>+</sup>on-n detectors are the technology choice

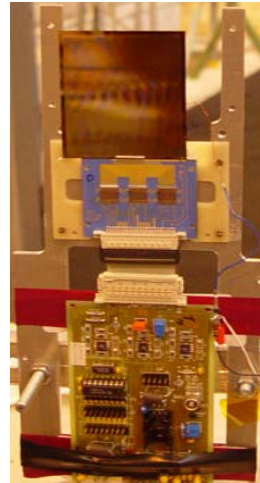
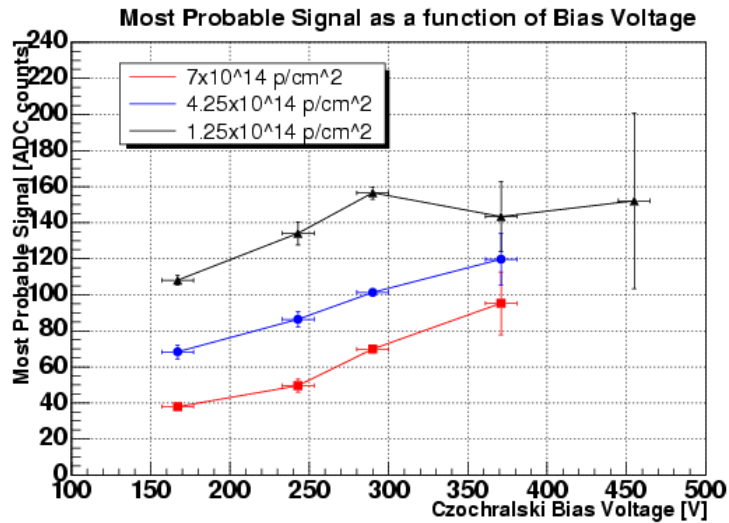


# Radiation Hard Technologies

- Cz, n-on-p, 3D, or pixel technologies – Active UK R&D

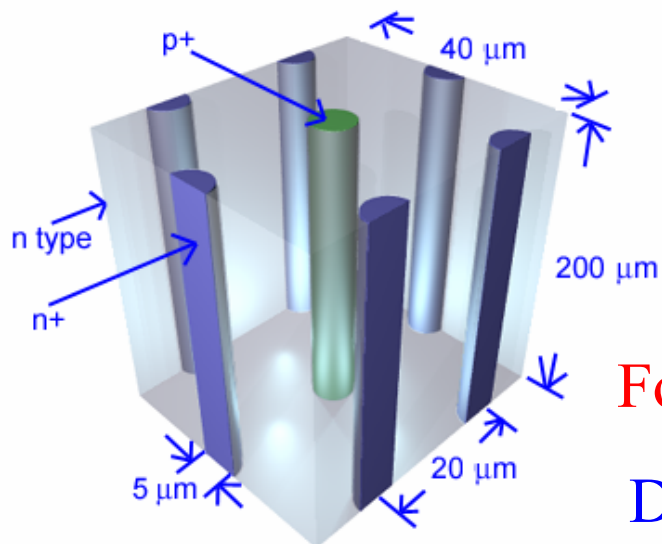
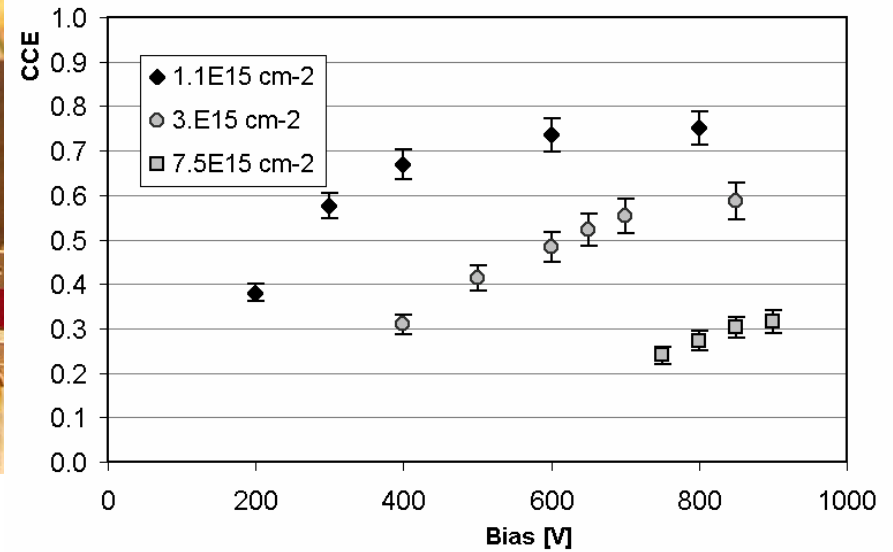
Czochralski

Glasgow, CERN



n-on-p

Liverpool



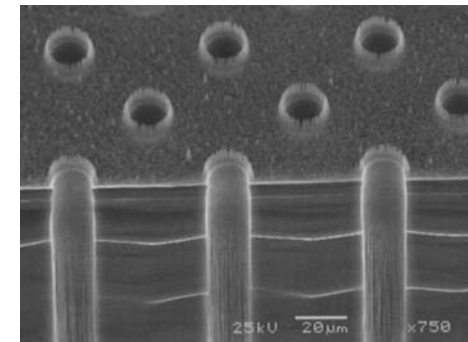
3D

Glasgow

Extreme rad. hard

For  $4.5 \times 10^{14}$  24 GeV p/cm<sup>2</sup>

Depletion voltage = 19V !!!





# The VELO stories continue...VESPA

- VELO upgrade...

Suggested  
name only

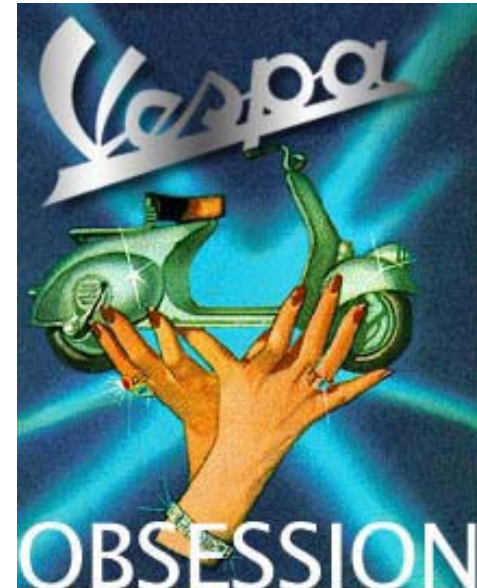


- **VElo Superior Performance Apparatus\***

- Just build the same again..?
- Many possibilities for VELO improvement and not just silicon changes.
- Silicon possibilities
  - n<sup>+</sup>on-p silicon
  - Magnetic Czochralski
  - 3D technology
  - Double sided
  - Strips or pixels?
  - ...?

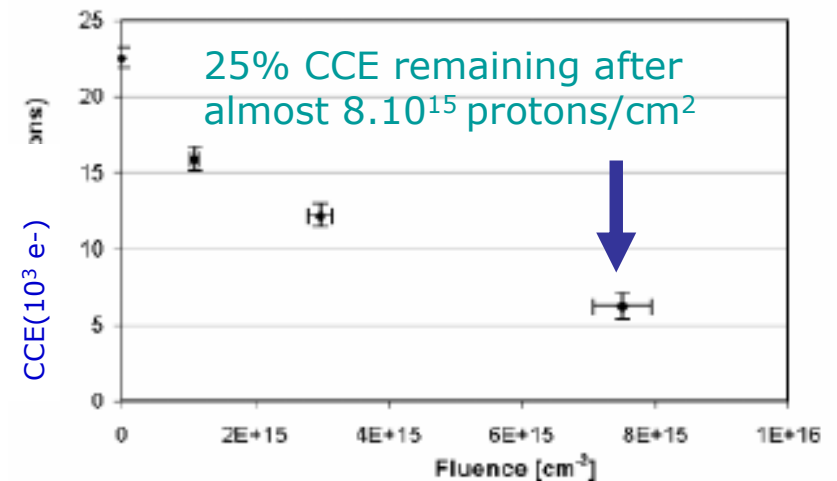


\*Chris Parkes, LHCb UK Meeting. 6<sup>th</sup> July 2004



# p<sup>+</sup>on-n, n<sup>+</sup>on-n or n<sup>+</sup>on-p?!

- p<sup>+</sup>on-n
  - Advantages
    - Standard processing (cheaper)
  - Disadvantages
    - Charge loss and charge spread after bulk type inversion
- n<sup>+</sup>on-n
  - Advantages
    - Operation under-depletion and after type inversion Electrons are collected instead of holes at the structured electrode and electrons are faster than holes -->less trapping
  - Disadvantages
    - Higher processing costs - requires double-sided imaging
- n<sup>+</sup>on-p
  - Advantages
    - Electric field always at the same implant
    - No double sided processing required
    - Operation under-depletion and after type inversion results in limited CCE and resolution loss
  - Disadvantages
    - Bulk starts p-type\*



\*There is also an acceptor removal which can (for low fluences) be stronger than the acceptor creation. Thus depletion voltage can go slightly down before it increases again.

# MCz silicon

Czochralski silicon appears to behave differently from DOFZ and FZ silicon

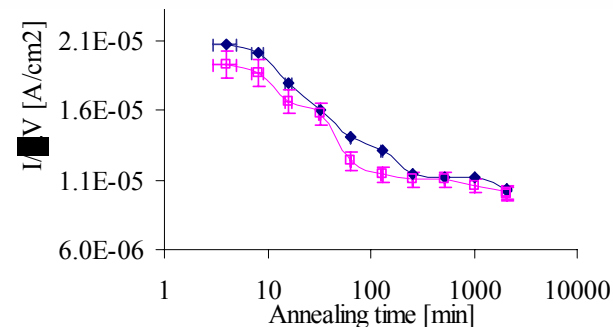
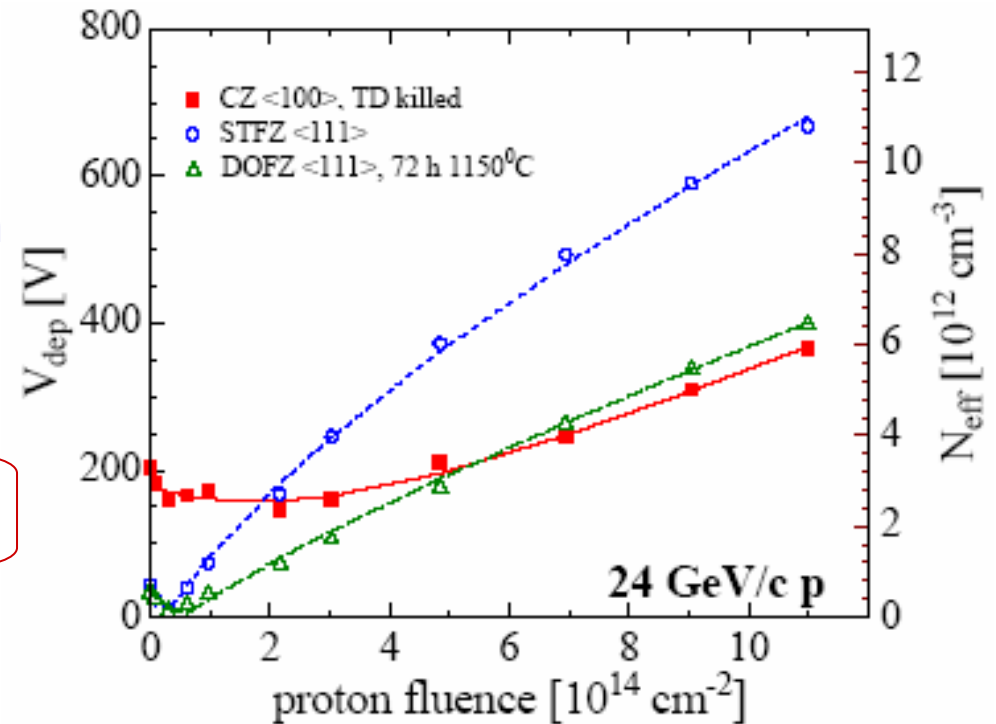
- **Surprises:**

- Many measurements have now shown MCz to be more radiation hard than DOFZ and FZ silicon
- MCz does not follow the same macroscopic behaviour – does MCz type invert?

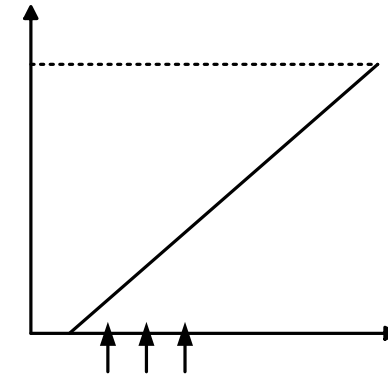
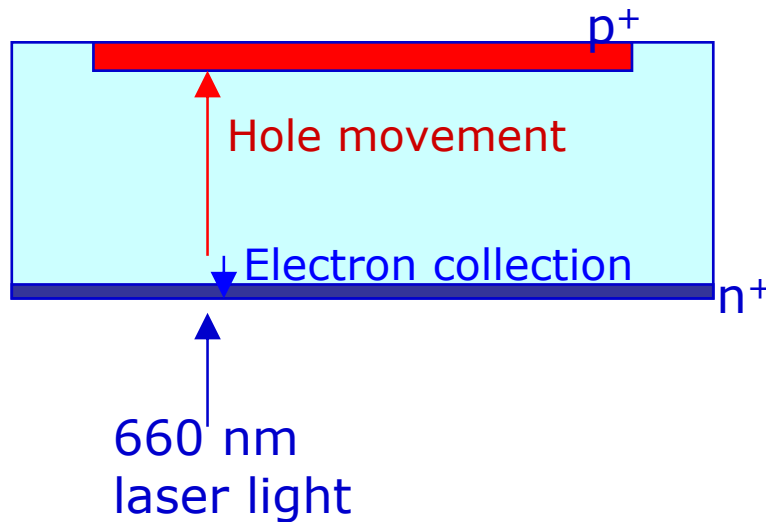
One of my studies...

- **Similarities:**

- Leakage current decreases with time after irradiation as usual
- CCE behaviour no different

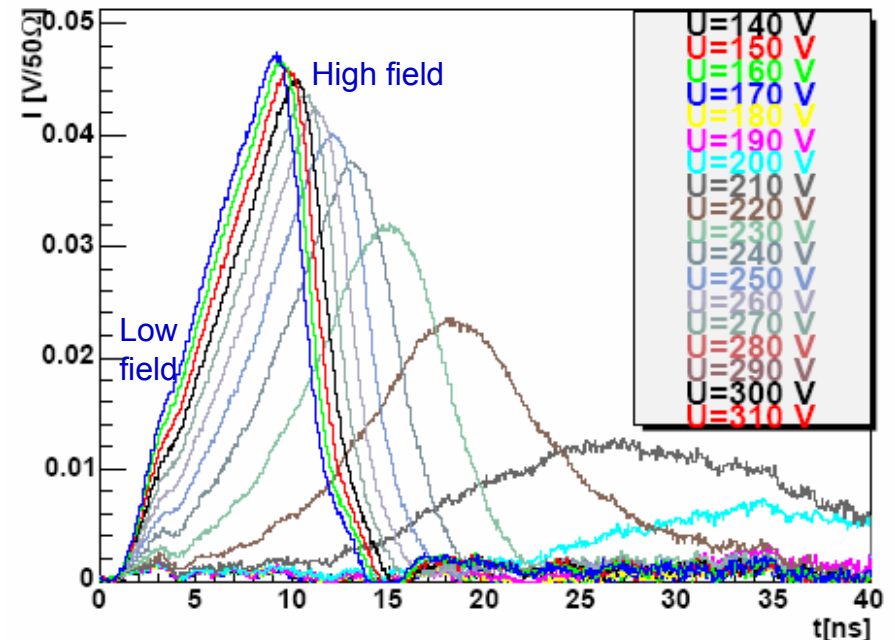


# Transient Current Technique



**Experiment which probes the electric field inside the silicon detector**

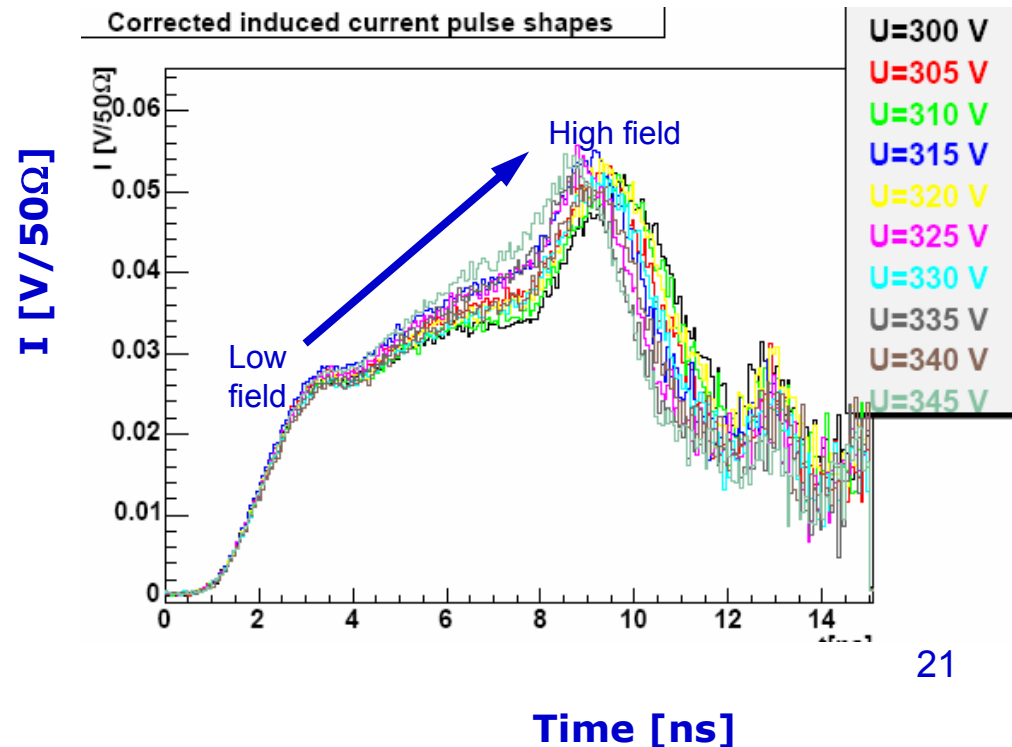
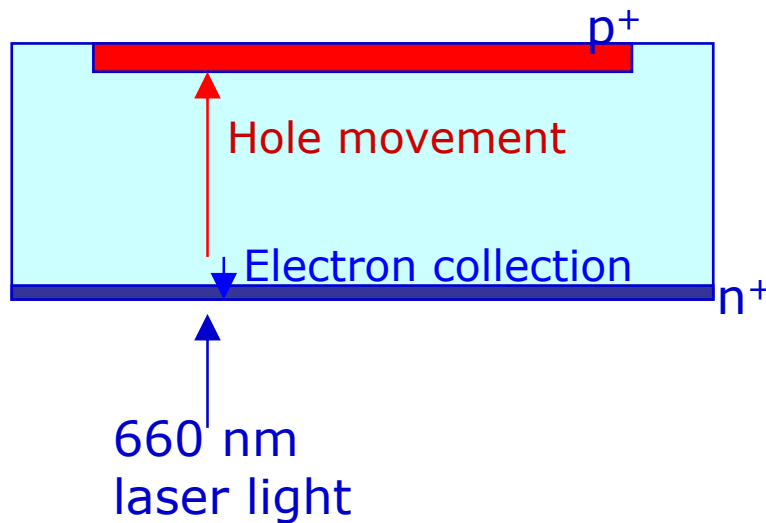
- Illuminate front (p<sup>+</sup>) or rear (n<sup>+</sup>) side of detector with 660 nm photons
- Light penetrates only a few  $\mu\text{m}$  depth
- Ramo's theorem dictates signal will be dominated by one type of charge carrier
- $I(t) = q E(v(t)) v(t)_{\text{drift}}$
- e.g. hole dominated current (hole injection)
  - Illuminate rear (n<sup>+</sup>) side of detector



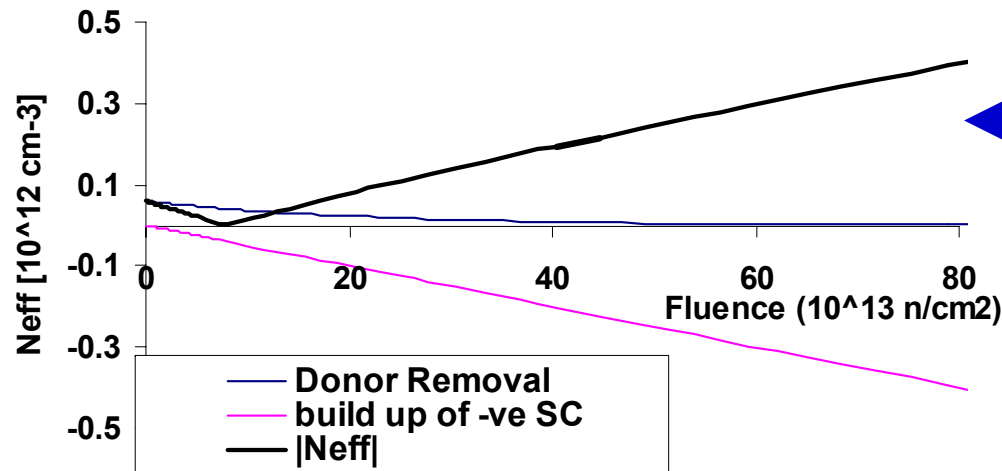
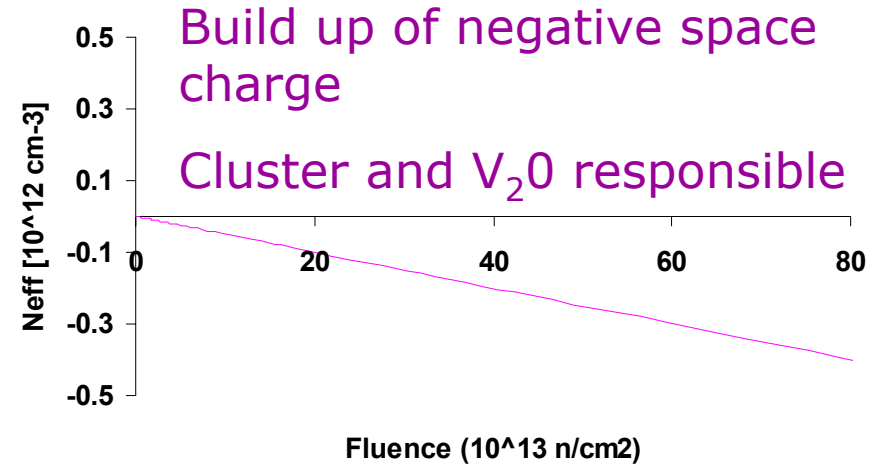
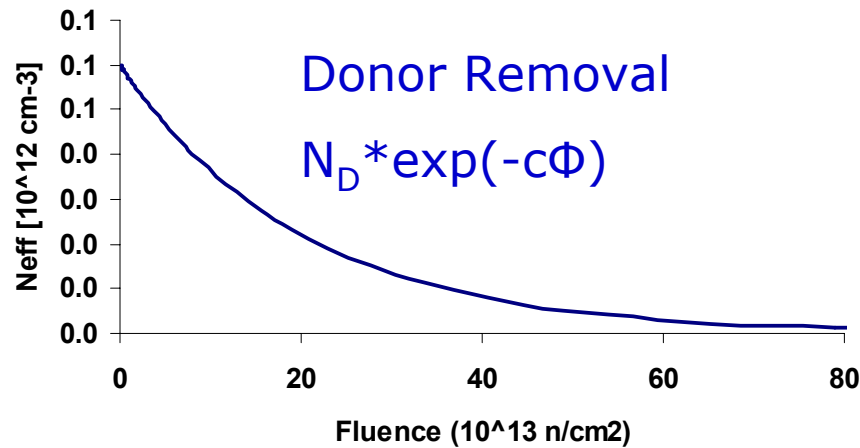
# MCz silicon

- After an irradiation level of  $5 \times 10^{14}$  p/cm<sup>2</sup>, the high electric field was still at the front p<sup>+</sup> implant.

Hence MCz-Si had not type inverted.

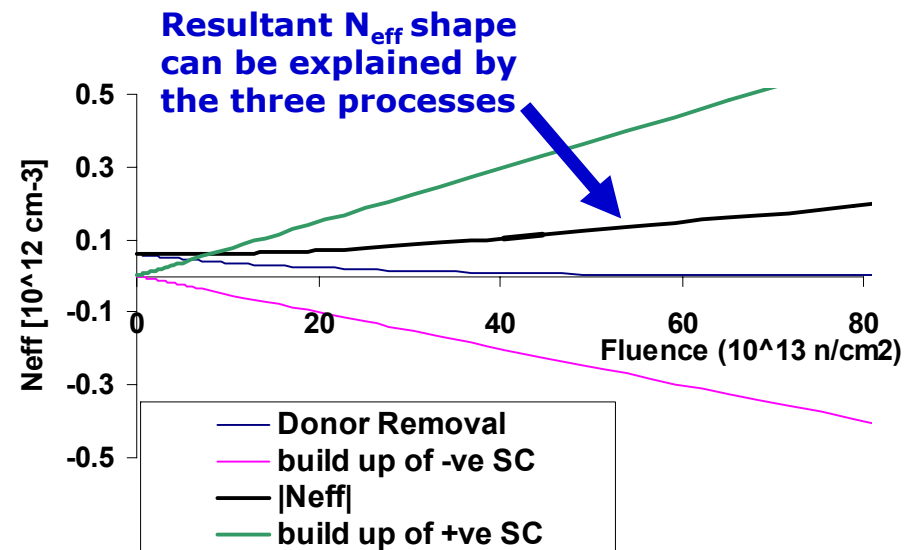
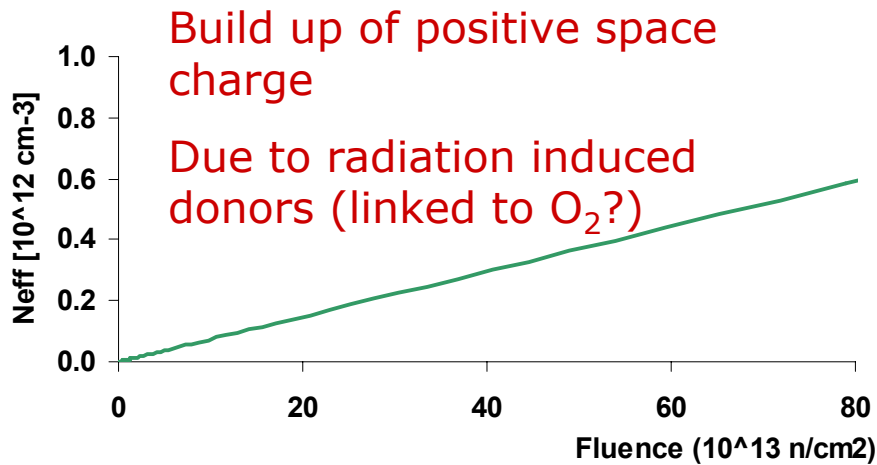
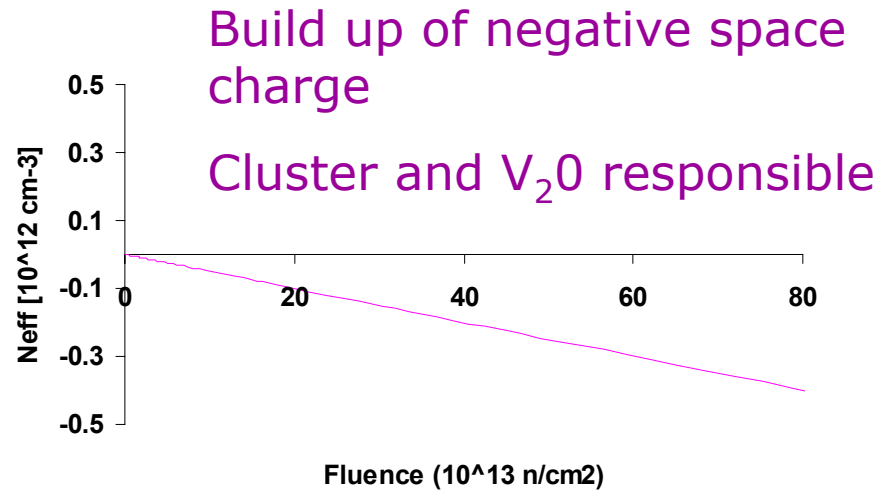
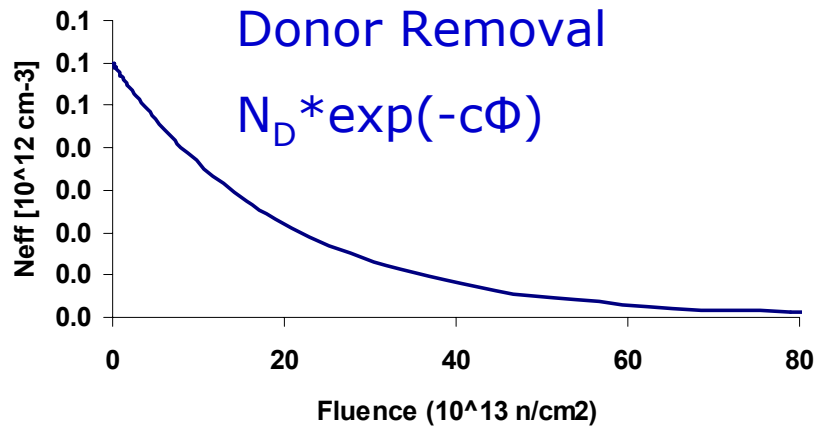


# Resultant $|N_{eff}|$ shape



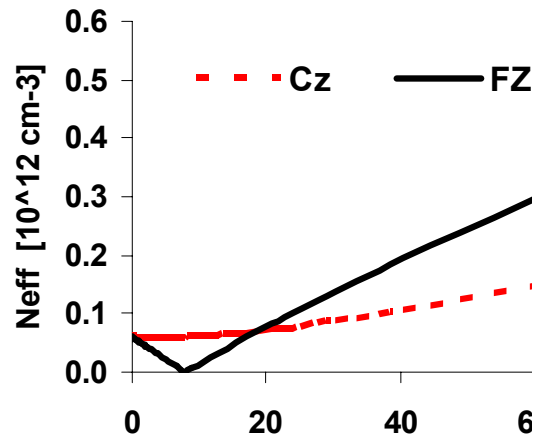
Resultant  $N_{eff}$  shape can be explained by the two processes

# Resultant Cz $|N_{eff}|$ shape



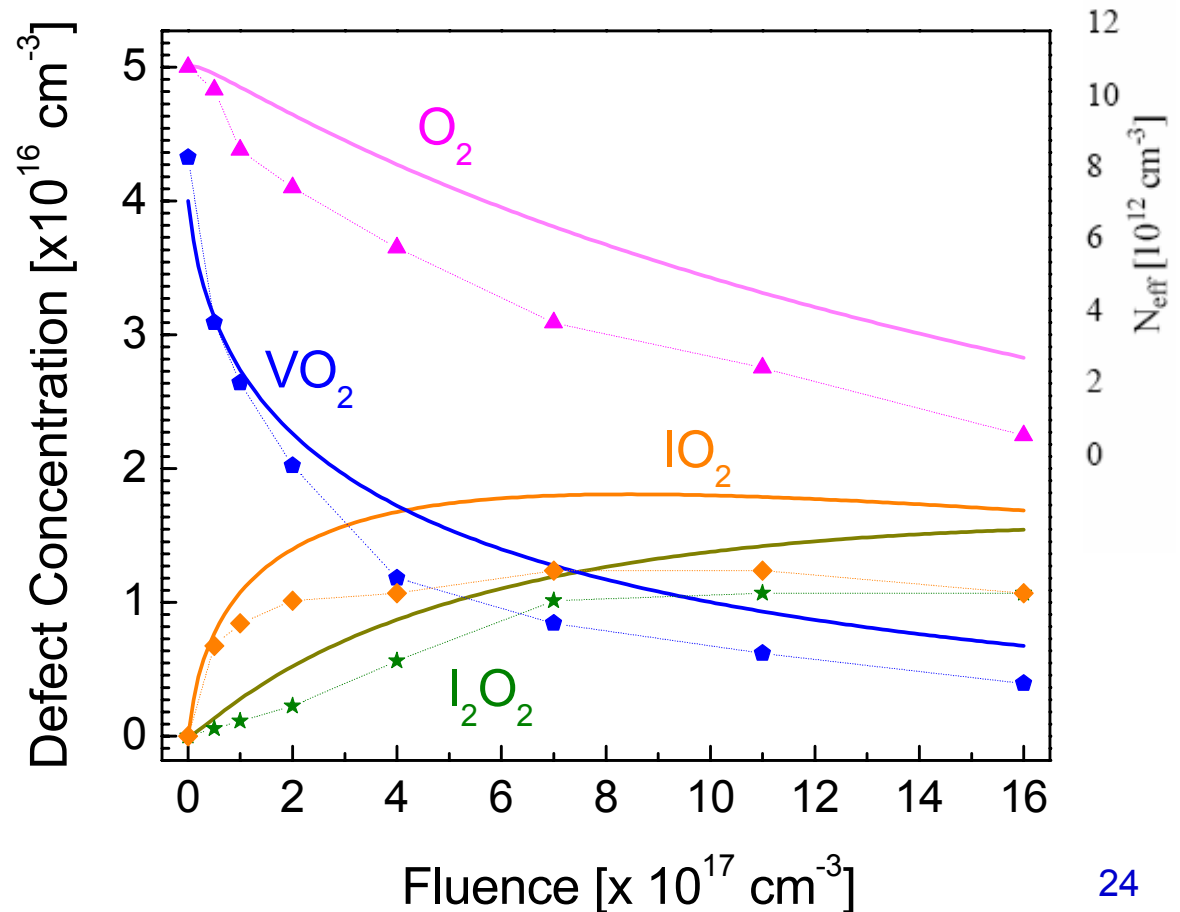
MCz has higher Oxygen content than FZ

# Fz/Cz differences



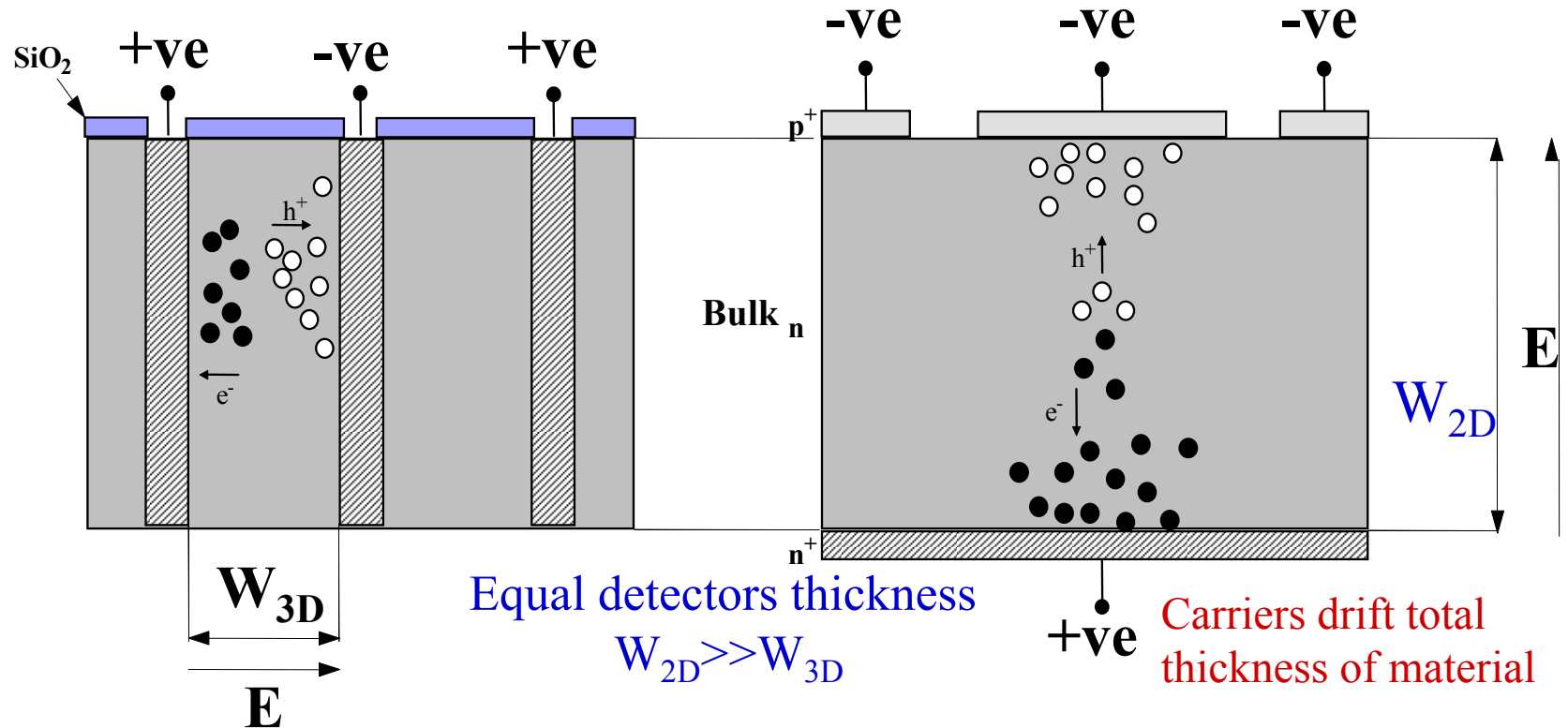
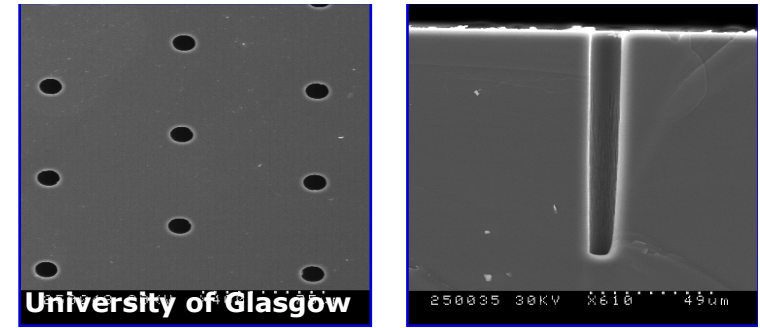
MCz

**Lots of research into defects to confirm these possible explanations**





# 3D technologies



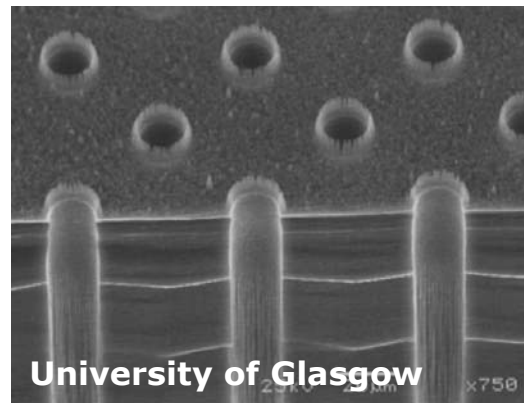
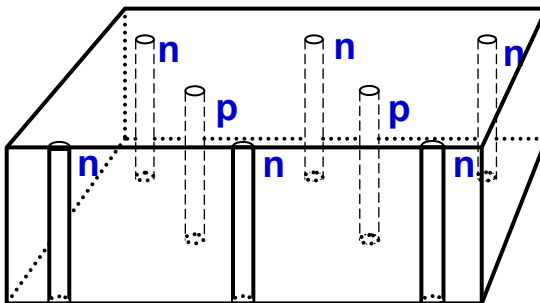
- narrow columns along detector thickness-“3D”
- diameter:  $10\mu\text{m}$  distance:  $50 - 100\mu\text{m}$ 
  - Lateral depletion:
    - lower depletion voltage needed
    - thicker detectors possible

Idea proposed by S. Parker

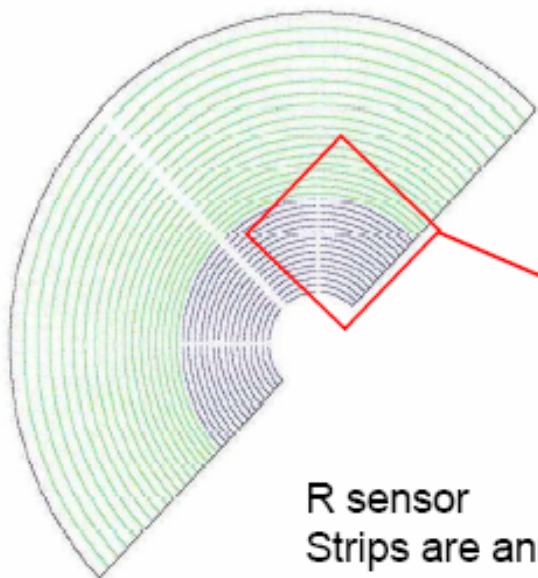
$$V_{dep} = \frac{q_0}{2\epsilon\epsilon_0} \cdot |N_{eff}| \cdot d^2$$



# 3D VESPA



## 3D strip detectors : VELO design



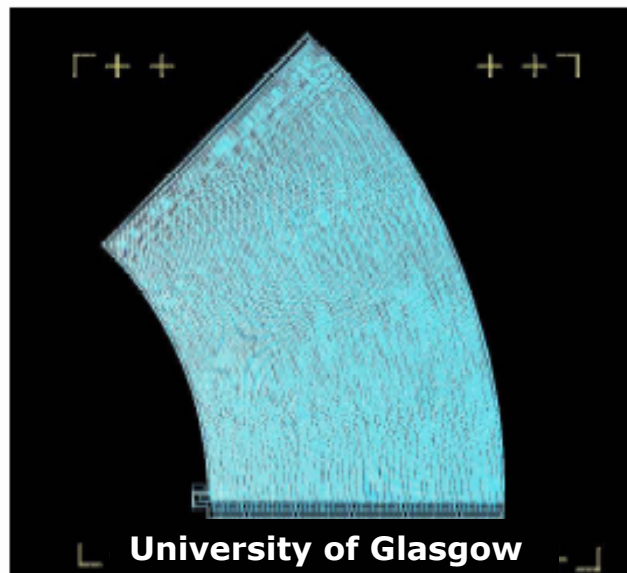
3D device

Pitch varies linearly from 45 $\mu$ m at the innermost region to 90 $\mu$ m at strip 128.

😊 Designed

😊 Fabricated

R sensor  
Strips are annular  
 $\pi/4$  segments  
R = 8mm to R = 42mm  
512 strips



Awaiting testing

R. Bates 5<sup>th</sup> Rd50 Workshop, October 2004, Florence